



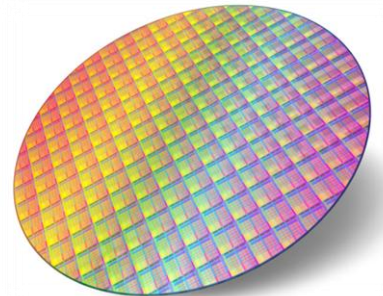
# AltiSurf<sup>®</sup>530

The AltiSurf<sup>®</sup> 530 has been priorly developped for Nanotechnology applications, having auto-alignment of wafer functions.

Same as all the 3D profilometer of the AltiSurf<sup>®</sup> range, the AltiSurf<sup>®</sup> 530 station incorporates the latest optical point or line sensor technologies and with its big size (300x300mm) it is very convenient for big parts and samples either in production or R&D.



**ALTIMET**



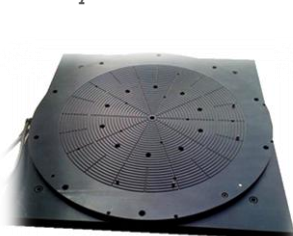
Technical	Specifications
Measurement Principle	Non-contact, Optical, based on Confocal Chromatic technology, Interferometric & other
Volume ( X x Y x Z)	300mm x 300mm x 100 mm (option Z 200mm or 300mm)
Speed of Stages	Up to 100mm/s
Flatness of Stages (Corrected)	2 μ/300mm (less than 1μ/300mm)
Measurement Range	From 100μm to 25mm
Resolution in Z	Down to 2nm
Lateral Resolution	0,7μm
Measuring Angle	Up to 90° ± 45° (optional Rotary Axis)
Step-Height Accuracy (1μm)	0,005 %
Low. Measurable roughness (Ra / Sa)	20nm / 20nm
Low. Measurable Thickness	1μm
Norm	ISO 4287, ISO 25178
Software	Acquisition : Phénix V2 / Analysis : PhénixMap

## Features & Advantages

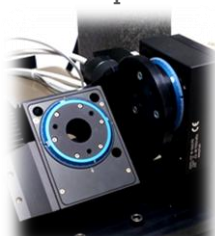
- Ability to measure every surfaces (rough, transparent, black, polished...)
- Vast choice of measurement range & technology (confocal, interfero, contact)
- Optical Measurement: no Damage to the measured part
- Max. 300x300x300mm measurement area
- Same resolution for each points – high accurate data
- Automatic swap between Camera and 2 other sensors
- Embedded measurement protocols
- Easy to use interface: automation of protocols



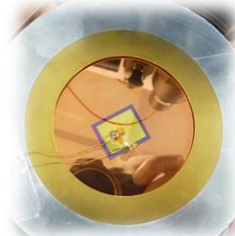
*PhéNIX V2 Technology*



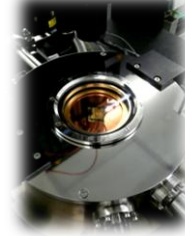
*Fixture for 8, 10, 12 inch Wafer*



*Rotary Axis*



*Vacuum measurement*



*Cryo ±200°C measurement*

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